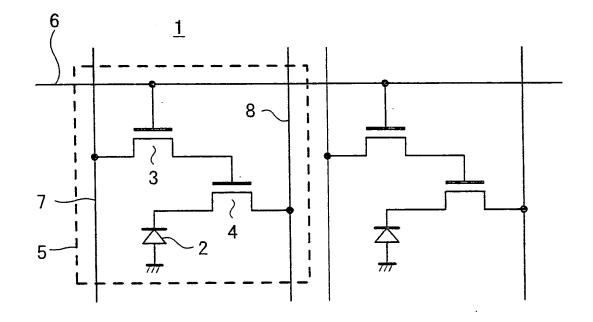
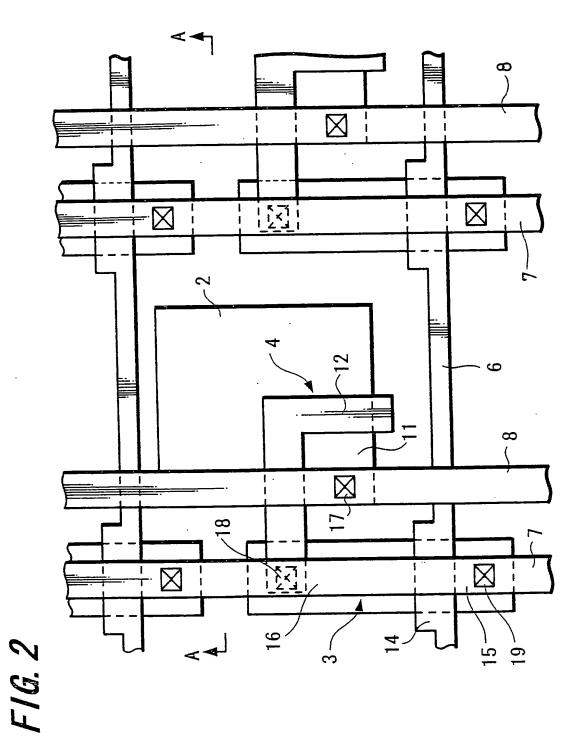
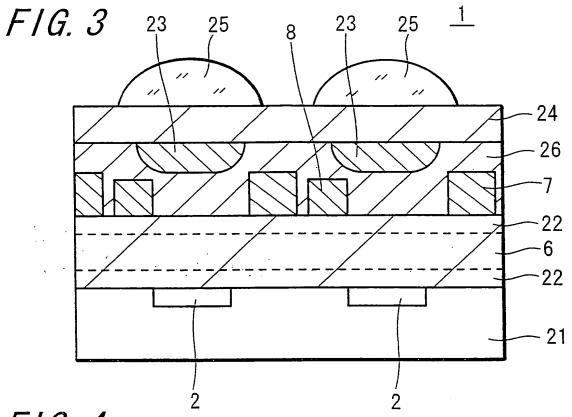
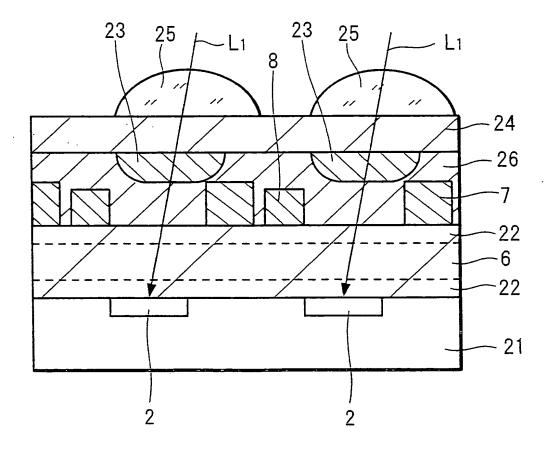
F/G. 1

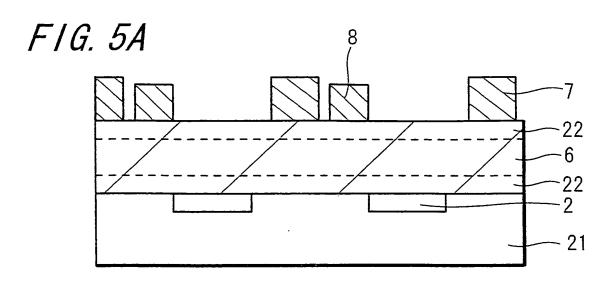


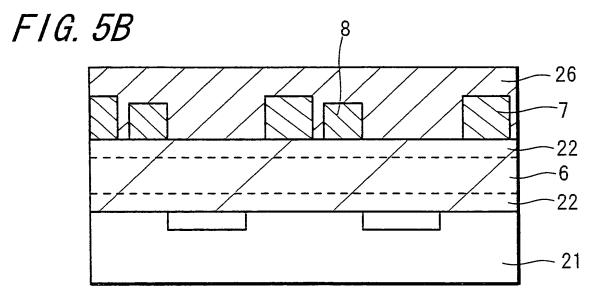


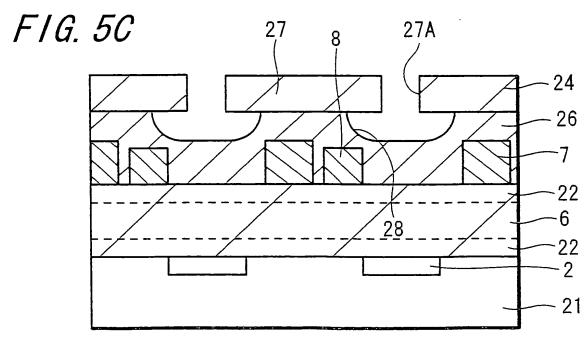


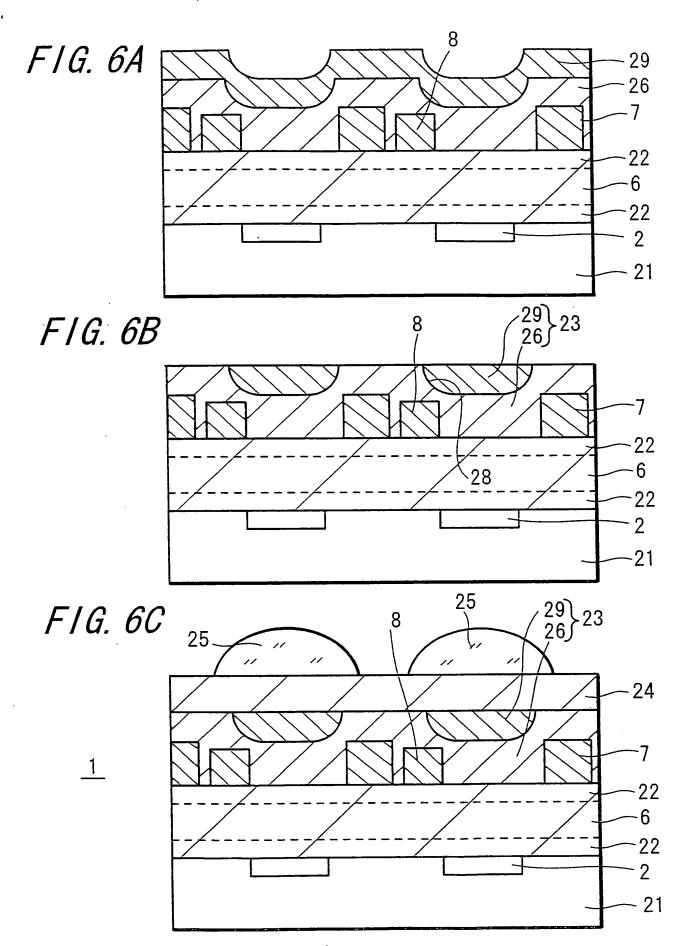
F/G. 4

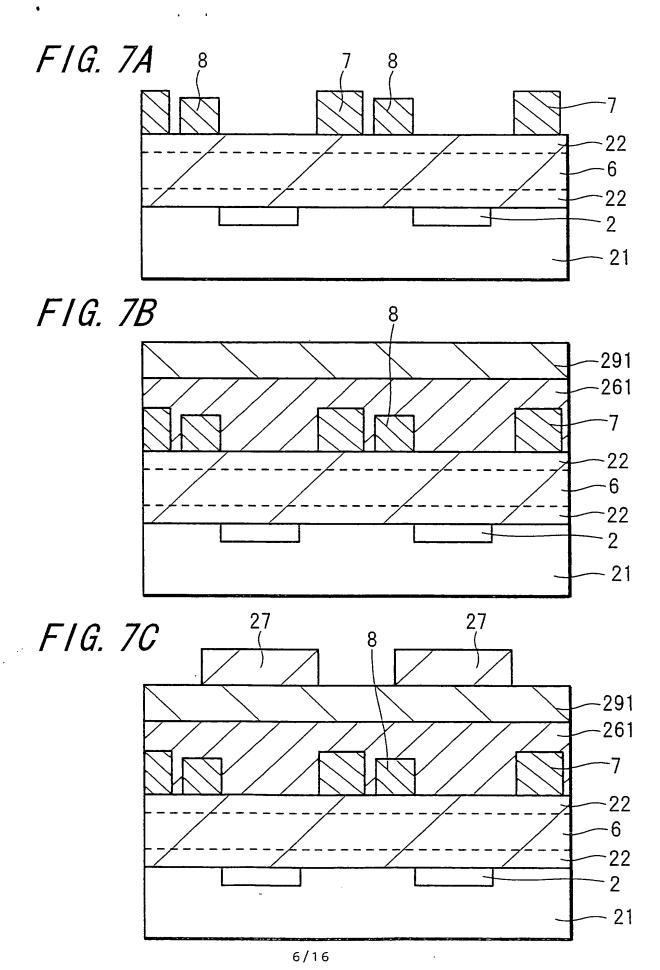


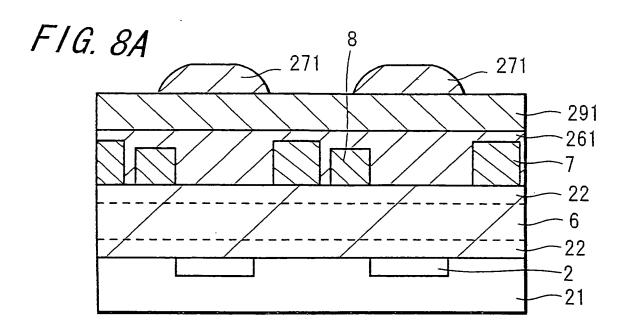


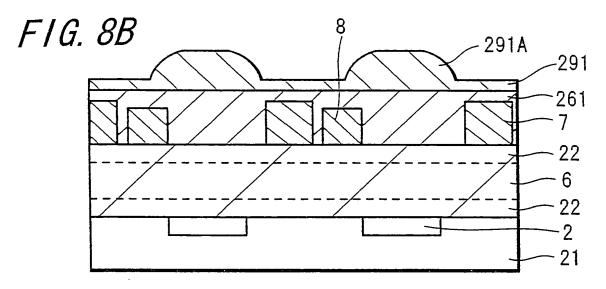












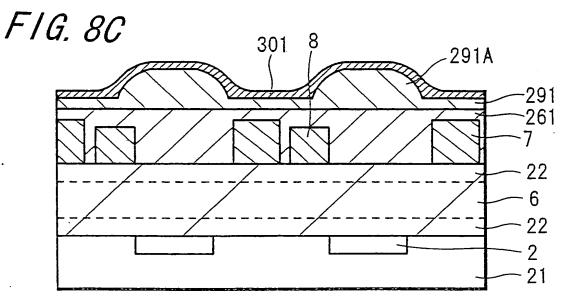
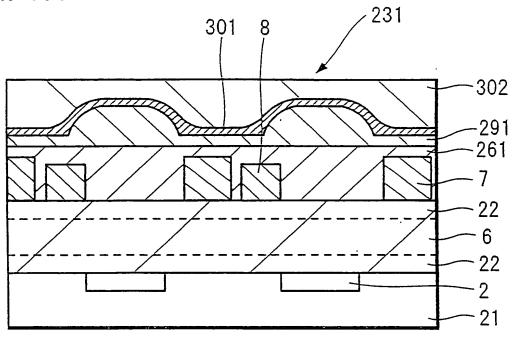
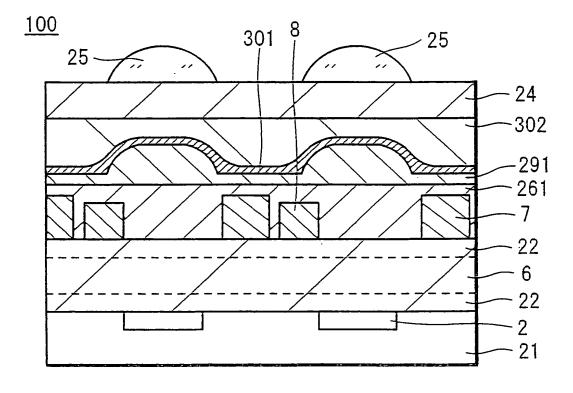


FIG. 9A

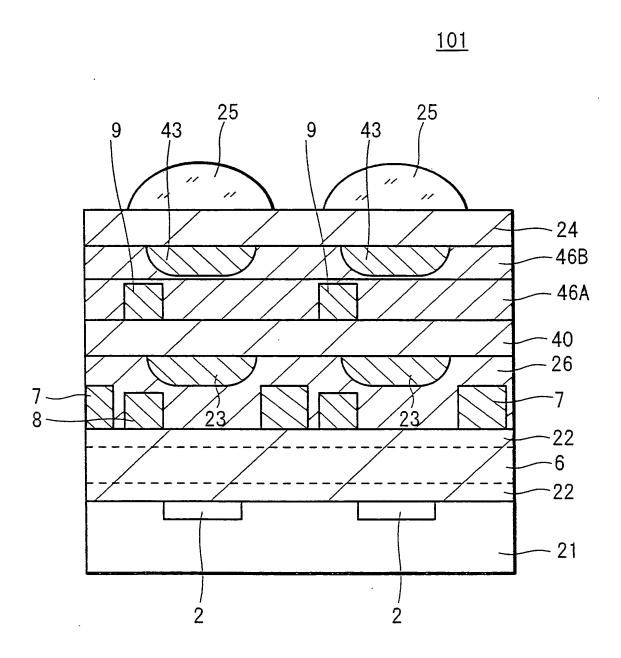


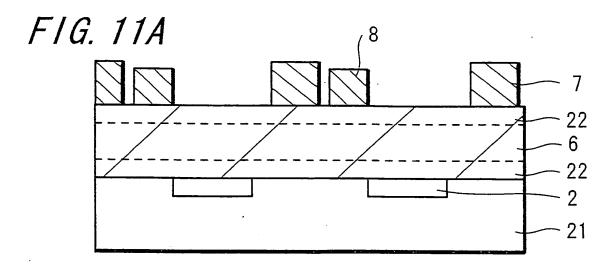
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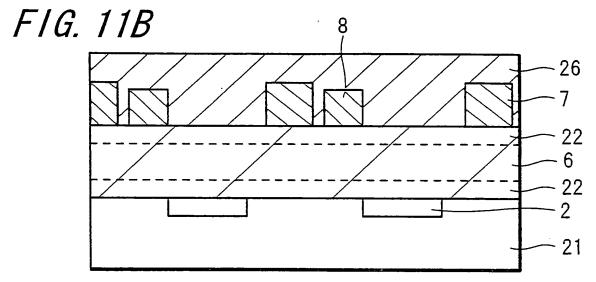
F1G. 9B

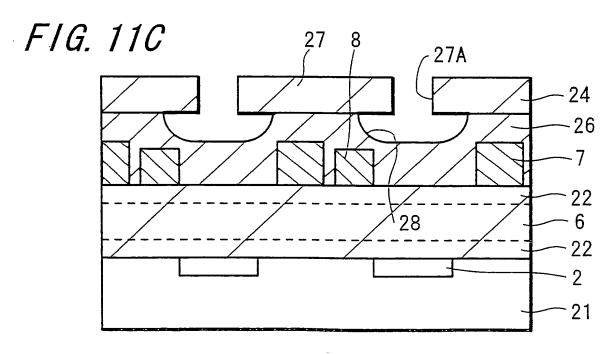


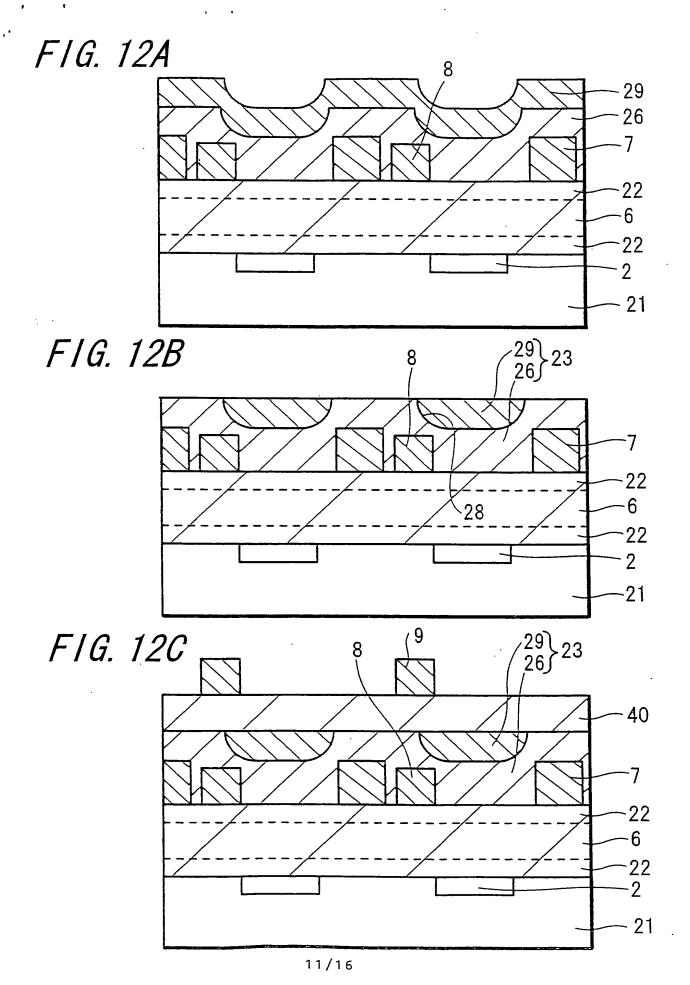
F/G. 10

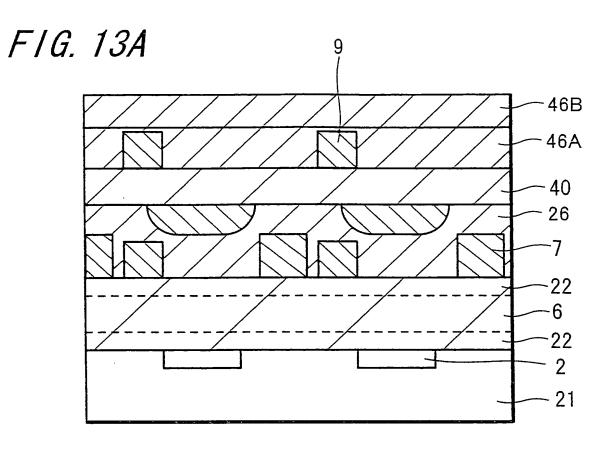


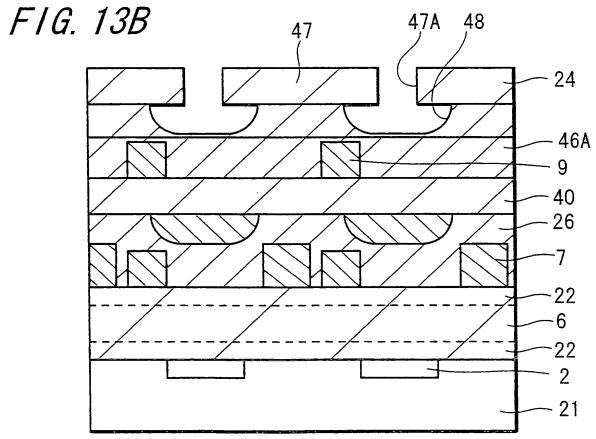




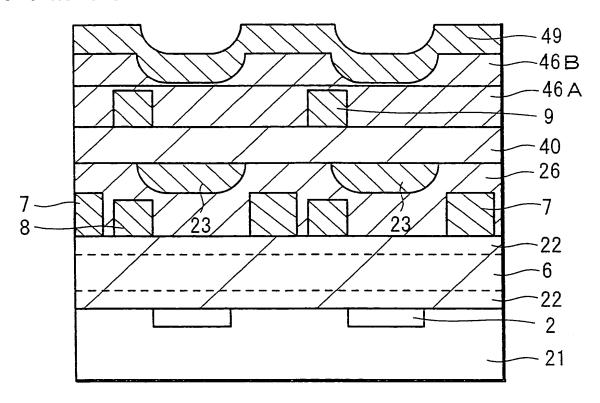


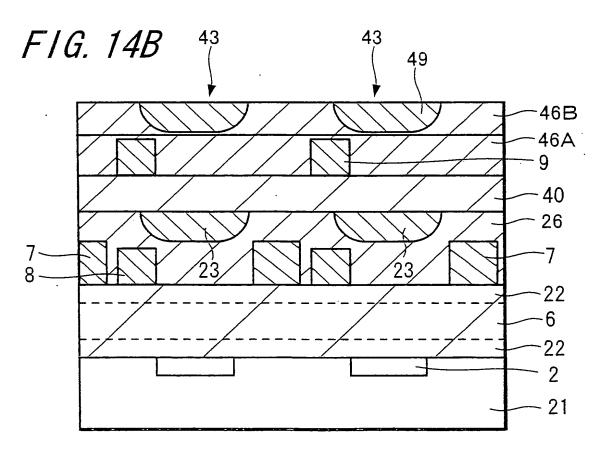






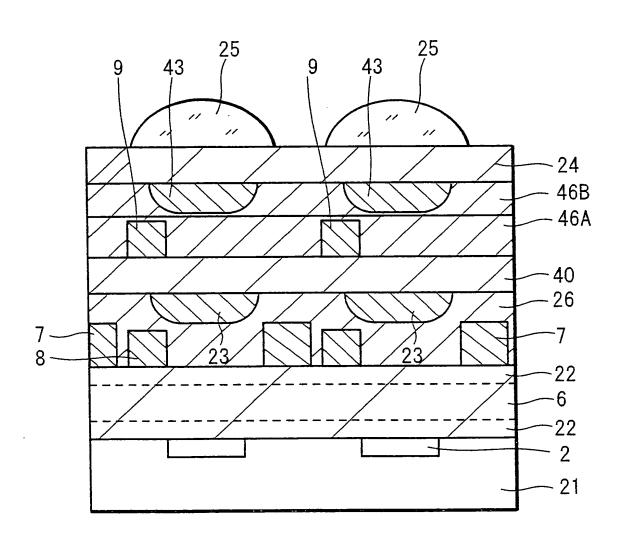
F/G. 14A





F/G. 15

<u>101</u>



Go State Comment

## DESCRIPTION OF REFERENCE NUMERALS

1		SOLID-STATE IMAGING DEVICE
2		LIGHT RECEIVING PORTION
3		VERTICAL SELECTION SWITCH ELEMENT
4		READOUT SWITCH ELEMENT
5		UNIT PIXEL
6		VERTICAL SELECTION LINE
7		READOUT PULSE LINE
8		VERTICAL SIGNAL LINE
9	• • • • •	WIRING
11		SEMICONDUCTOR REGION
12		GATE ELECTRODE
14		GATE ELECTRODE
15		ONE REGION
16		THE OTHER REGION
21		SEMICONDUCTOR ELECTRODE
22		INTRA-LAYER INSULATION LAYER
23	••••	INTRA-LAYER CONDENSING LENS
24		COLOR FILTER
25	• • • • •	ON-CHIP MICRO LENS
26		FIRST INSULATION LAYER
27		RESIST MASK
27A		OPENING
28		CONCAVE PORTION
29		SECOND INSULATION LAYER

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40		INTRA-LAYER INSULATION LAYER
43	• • • • • •	INTRA-LAYER CONDENSING LENS
46A		INSULATION LAYER
46B		THIRD INSULATION LAYER
47		RESIST MASK
47A		OPENING
100		SOLID-STATE IMAGING DEVICE
101		SOLID-STATE IMAGING DEVICE
231		INTRA-LAYER CONDENSING LENS
261	• • • • •	FIRST PLANARIZING FILM
271		REFLOW FILM
291	• • • • •	FIRST INSULATION LAYER
291A	• • • • •	CONVEX PORTION
301	• • • • •	SECOND INSULATION LAYER
302		SECOND PLANARIZING FILM